

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Hiromitsu Tsuji et al.

Application No.: 10/581,777

Confirmation No.: 7141

Filed: June 6, 2006

Art Unit: 1753

For: Photoresist Composition And Method Of
Forming Resist Pattern

Examiner: Ponder N. Thompson
Rummel

AMENDMENT IN RESPONSE TO FINAL OFFICE ACTION

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

INTRODUCTORY COMMENTS

In response to the Office Action dated March 19, 2008, please amend the above-identified U.S. patent application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 5 of this paper.